

filed 7/25/03

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

SYSTEM AND METHOD OF ALTERING A VERY SMALL
SURFACE AREA BY MULTIPLE CHANNEL PROBE

Application Number : 10/604,486
Confirmation Number:
First Named Applicant: Hendrik Hamann
Attorney Docket Number: FIS920020170US1
Art Unit: 1765
Examiner: Alanko
Search string: (5865978 or 6002471 or 4880496 or 6078055).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
AKC	1	5865978	1999-02-02	Cohen		205	118
	2	6002471	1999-12-14	Quake		356	73
	3	4880496	1989-11-14	Nebenzahl, et al.		216	93
↓	4	6078055	2000-06-20	Bridger, et al.	AKC	250	442.2

Signature

Examiner Name	Date
<i>Alanko</i>	6/20/05

<div style="text-align: center;"> <p>filed 8/14/03</p> <p>OPEN INFORMATION DISCLOSURE CITATION</p> <p>(Use several sheets if necessary)</p> <p>AUG 14 2003</p> </div>		Docket Number (Optional)		Application Number	
		FIS920020170US1		10/604,486	
		Applicant(s)			
		Hendrik F. Hamann et al.			
Filing Date		Group Art Unit			
07/25/2003		1765			
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Anita Glanko			6/20/05		
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.					

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Docket Number (Optional)

FIS9200201.7QUS1

Application Number

10/604,48'6

Applicant(s)

Hendrik F. Hamann et al.

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